#### **Electronics for IoT**

#### **Semiconductors**

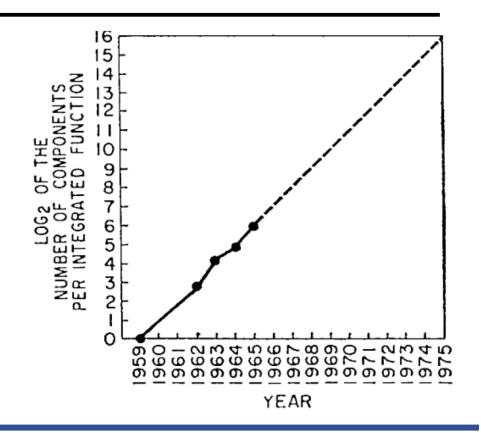
Bernhard E. Boser
University of California, Berkeley
<a href="mailto:boser@eecs.berkeley.edu">boser@eecs.berkeley.edu</a>

#### Moore's Law

# **Cramming More Components onto Integrated Circuits**

GORDON E. MOORE, LIFE FELLOW, IEEE

Electronics, April 19, 1965





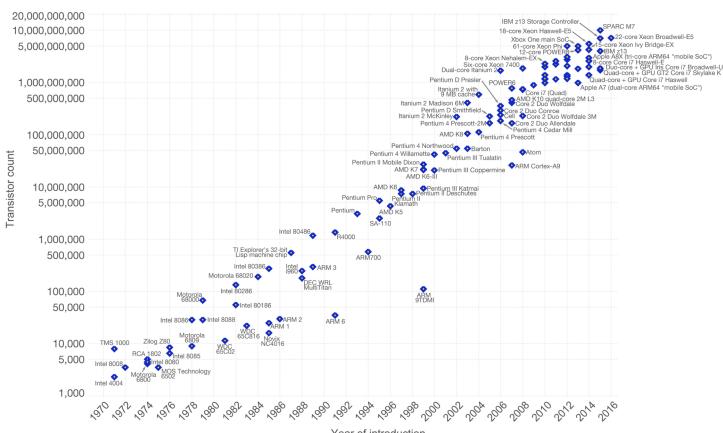
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#### **Number of Transistors**

#### Moore's Law – The number of transistors on integrated circuit chips (1971-2016)



Moore's law describes the empirical regularity that the number of transistors on integrated circuits doubles approximately every two years. This advancement is important as other aspects of technological progress – such as processing speed or the price of electronic products – are strongly linked to Moore's law.



Year of introduction

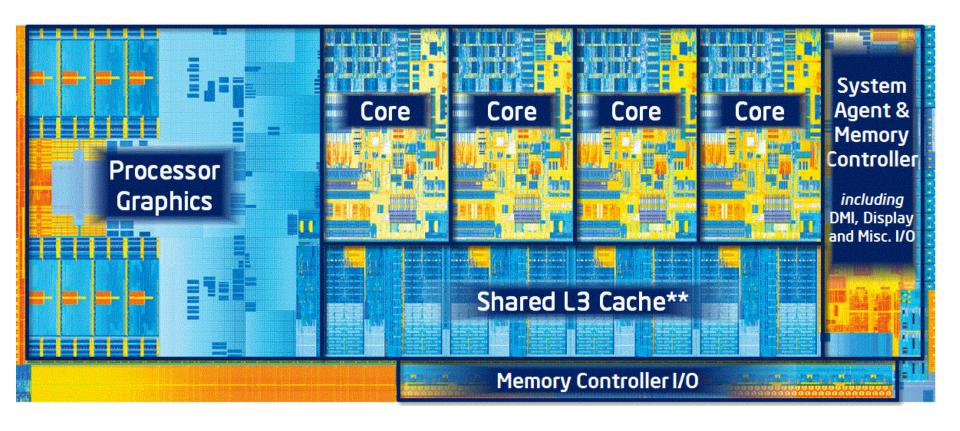
Data source: Wikipedia (https://en.wikipedia.org/wiki/Transistor\_count) The data visualization is available at OurWorldinData.org. There you find more visualizations and research on this topic.

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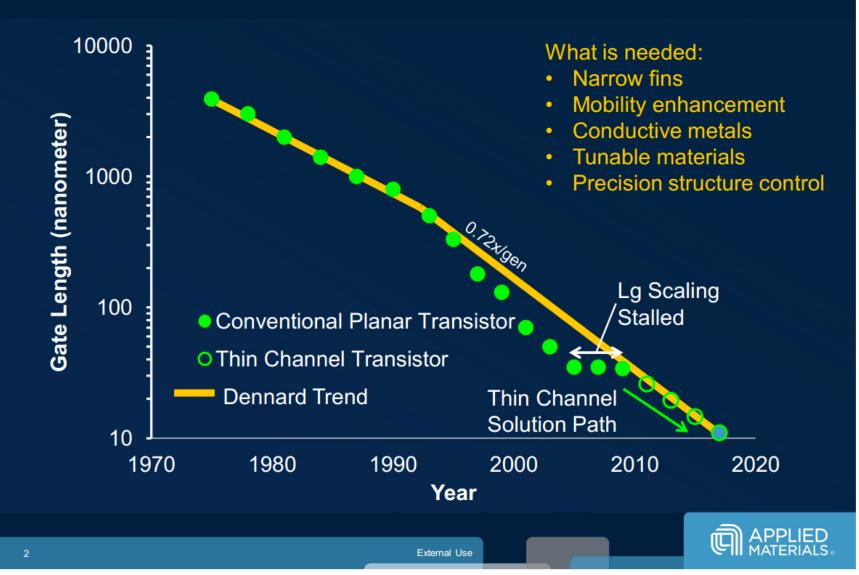
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#### **Processor**





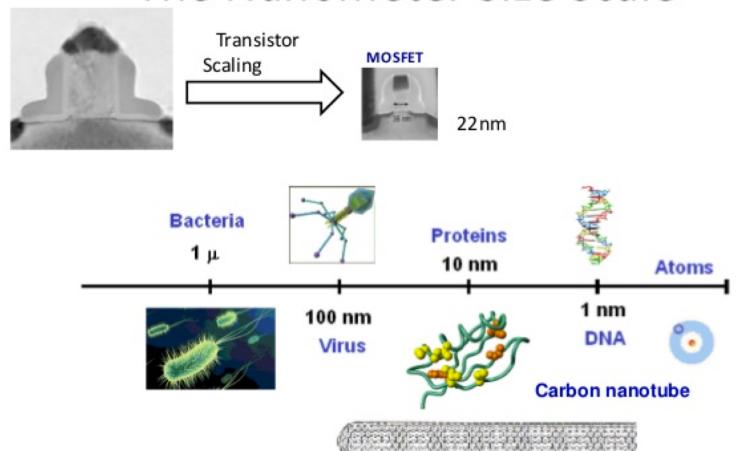
## **Continue The Lg Scaling Path**





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#### The Nanometer Size Scale



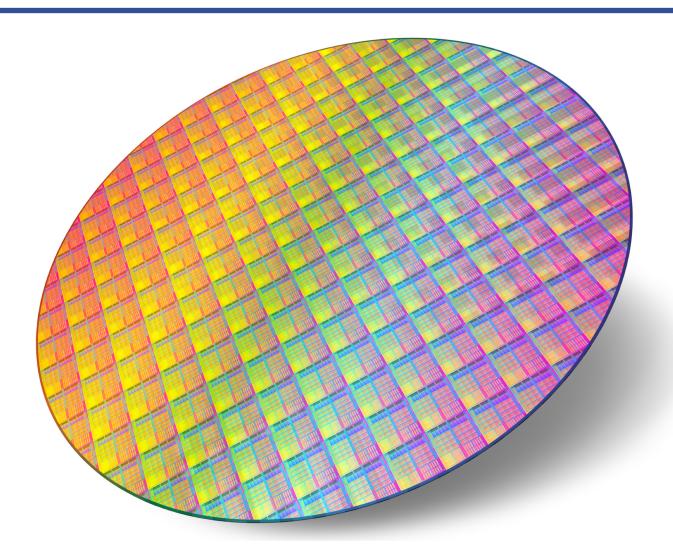
Scaling cannot go on forever because transistors cannot be smaller than atoms

# **Yield**



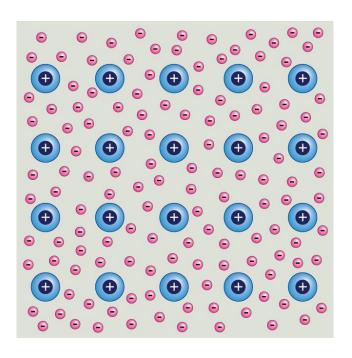
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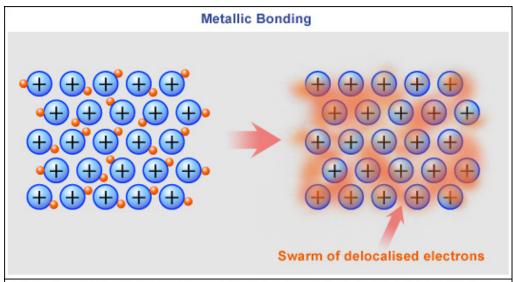
# Silicon Wafer





#### **Metals**



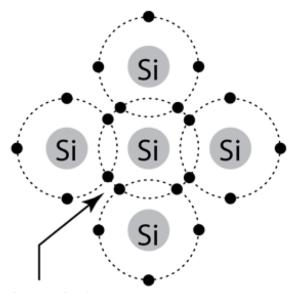


The outer electrons are so weakly bound to metal atoms that they are free to roam across the entire metal. Having 'lost' their outer electrons, individual metal atoms are more like positive ions in a swarm of communal electrons.

# **Insulators**

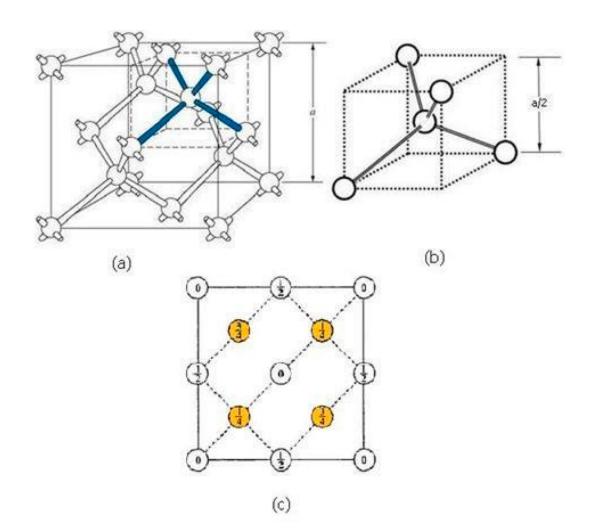


# **Semiconductors**



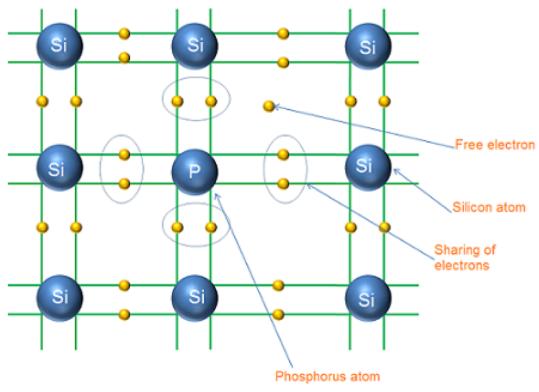
Shared electrons of a covalent bond.

## **Lattice Constant**



Material	Lattice constant (Å)	
C (diamond)	3.567	
C (graphite)	a = 2.461 c = 6.708	
Si	5.431	
Ge	5.658	
AlAs	5.6605	
AIP	5.4510	
AISb	6.1355	
GaP	5.4505	
GaAs	5.653	
GaSb	6.0959	
InP	5.869	

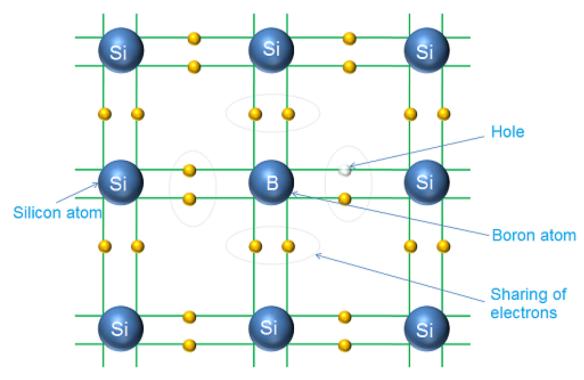
# **N-type Semiconductors**



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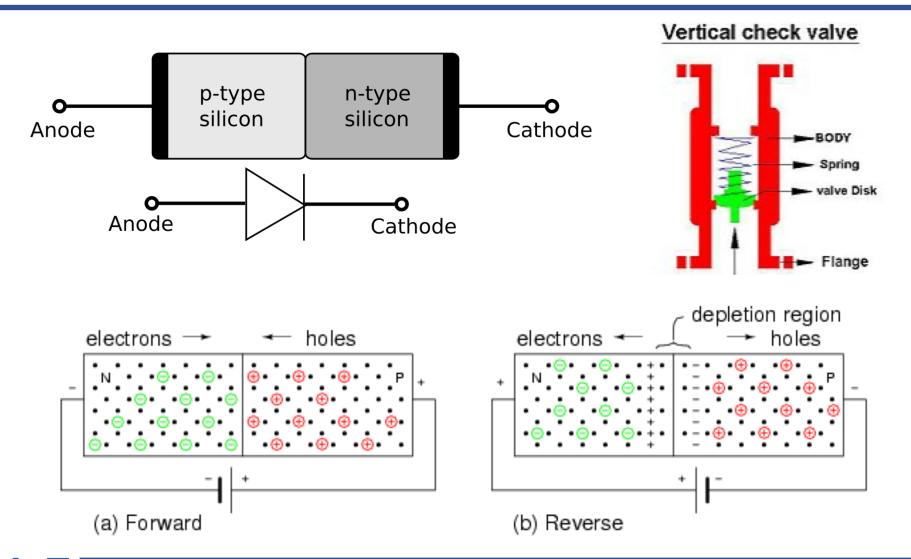
# P-type Semiconductors



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#### **Diodes**



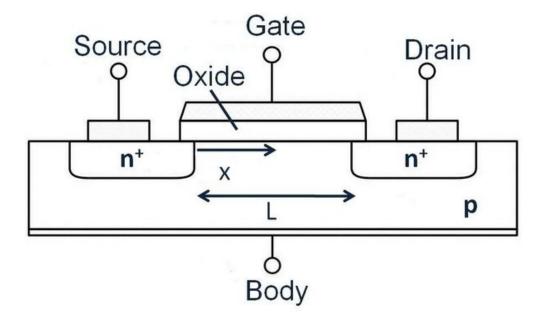


# Field Effect Transistor (FET)



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# MOSFET Metal Oxide Semiconductor FET



# Switch Logic – Example: Adder



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# **Switch Logic**

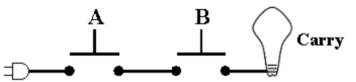
#### **Building an Adder with Switches**

Now that you are comfortable adding binary numbers together, let's see how we could make an adding machine using transistors. We will use simple light switches here to make things clearer—but this is not an oversimplification: the transistor logic works very similarly. For this example, we will build part of an adding machine that can add two binary digits (bits) together.

Here are the possible answers obtained from adding two bits:

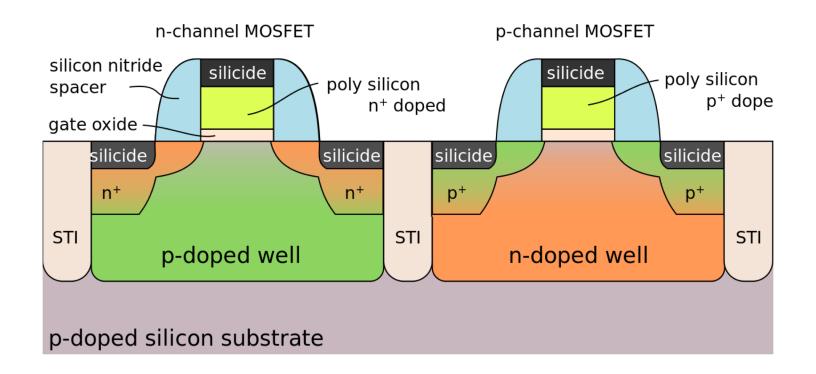
Α	В	Ca	rry Sum
		0	0
0	1	0	1
1	0	0	1
1	1	1	0

We'll just design the "Carry" output of the adder here (the Sum is a bit harder, but also can be done using only transistor switches). The Carry is 1 only if both of our inputs are 1. That is, the Carry is 1 when input A **AND** input B are 1. Thus we can use two switches in a row just as shown above to build the Carry output of our adding machine.



Using combinations of transistor switches, we can build circuits to add, subtract, multiply, and divide. We can also use them to make very simple decisions, by using the logical **AND** or the logical **OR** functions.

#### **CMOS**



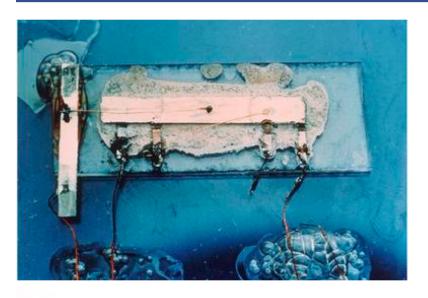


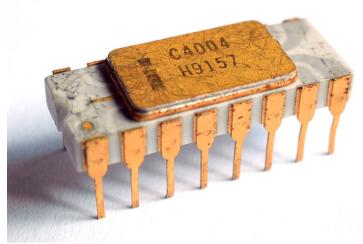
# **Acronyms**

- Transistor
  - Semiconductor device
- Field Effect Transistor (FET)
  - Specific physical implementation
  - Alternative: Bipolar Junction Transistor (BJT)
- Metal Oxide FET (MOSFET)
  - Particular realization of FET
- NMOS, PMOS
  - Types of MOSFET transistors
- CMOS
  - Process capable of fabricating NMOS and PMOS FETs

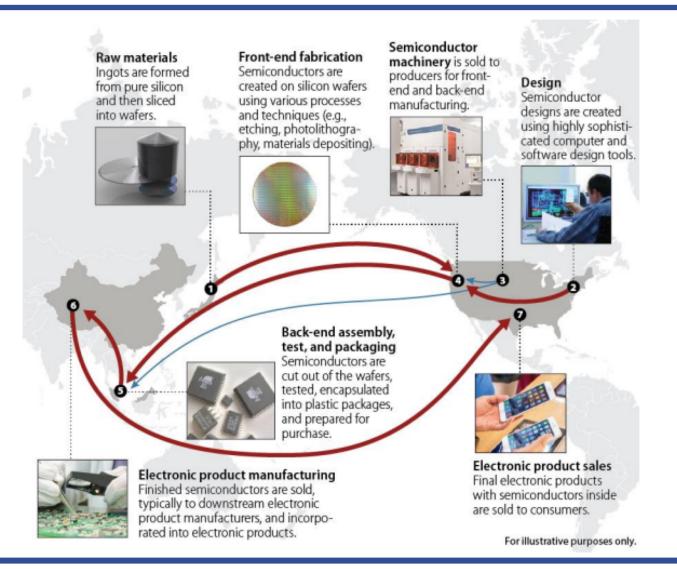


# **Batch Fabrication**





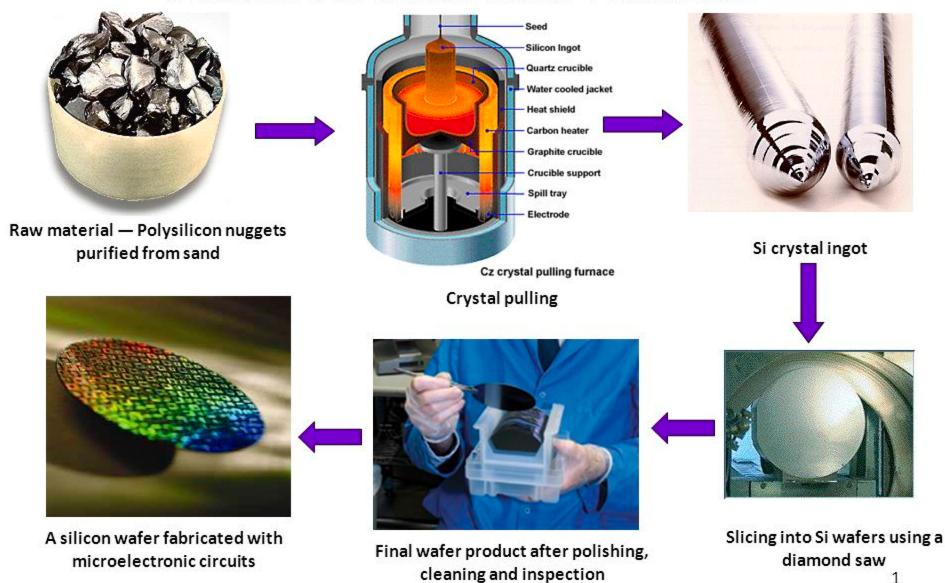
#### **Semiconductor Production**



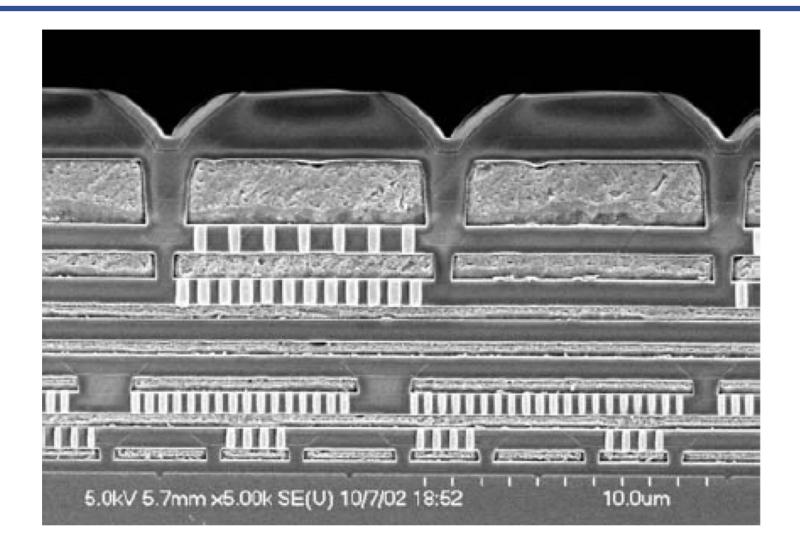


#### **IC Fabrication Overview**

#### **Procedure of Silicon Wafer Production**



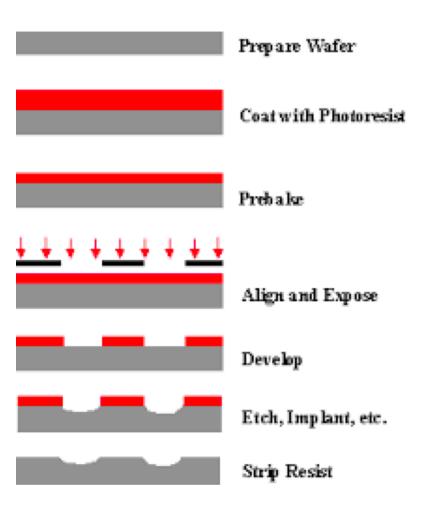
#### **Processed Silicon Wafer Cross-Section**





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# Lithography





# **Example 1: XTR Junctions**



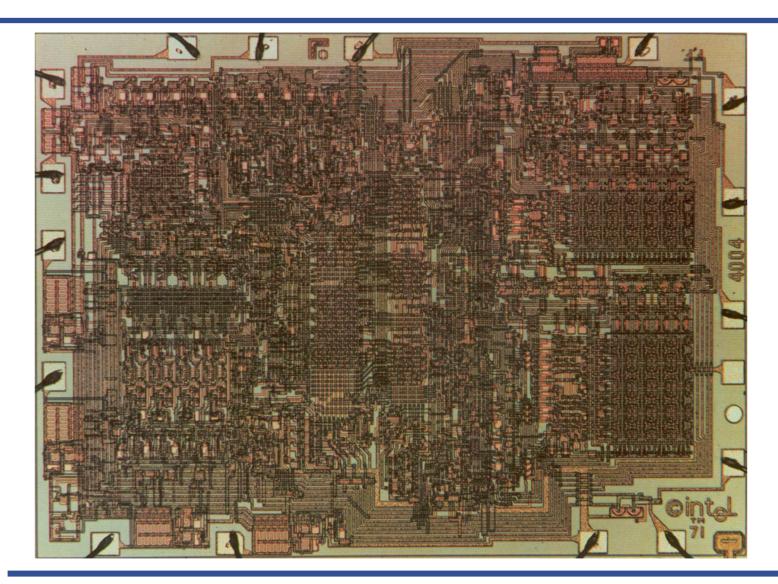
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# **Example 2: Interconnect**



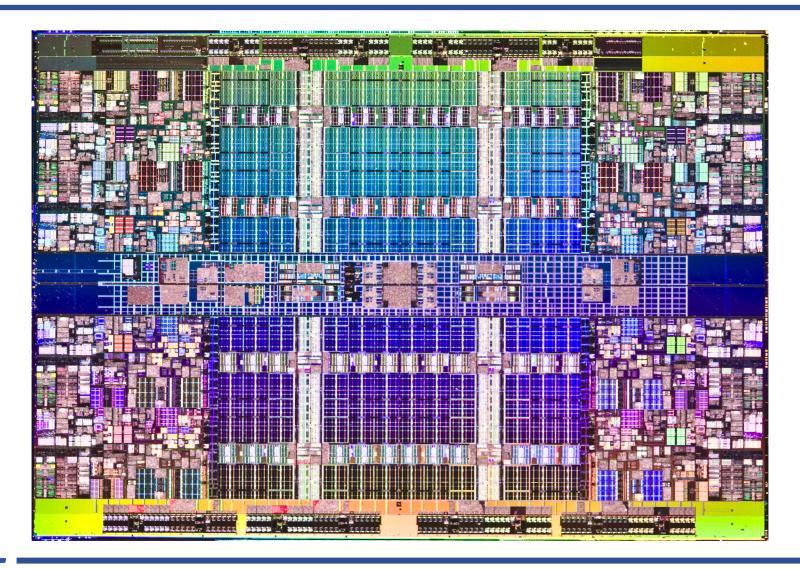
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# Result





## More of same ...





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#### Silicon as a Mechanical Material

KURT E. PETERSEN, MEMBER, IEEE

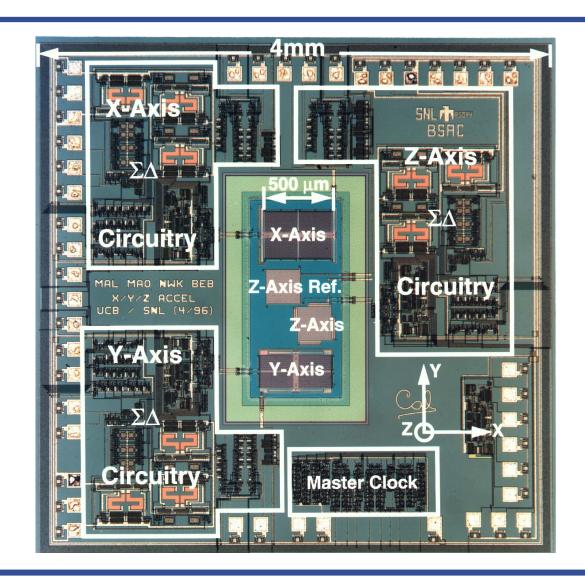
Abstract-Single-crystal silicon is being increasingly employed in a variety of new commercial products not because of its well-established electronic properties, but rather because of its excellent mechanical properties. In addition, recent trends in the engineering literature indicate a growing interest in the use of silicon as a mechanical material with the ultimate goal of developing a broad range of inexpensive, batch-fabricated, high-performance sensors and transducers which are easily interfaced with the rapidly proliferating microprocessor. This review describes the advantages of employing silicon as a mechanical material, the relevant mechanical characteristics of silicon, and the processing techniques which are specific to micromechanical structures. Finally, the potentials of this new technology are illustrated by numerous detailed examples from the literature. It is clear that silicon will continue to be aggressively exploited in a wide variety of mechanical applications complementary to its traditional role as an electronic material. Furthermore, these multidisciplinary uses of silicon will significantly alter the way we think about all types of miniature me chanical devices and componenta

I. Introduction

miniaturized mechanical devices and components must be integrated or interfaced with electronics such as the examples given above.

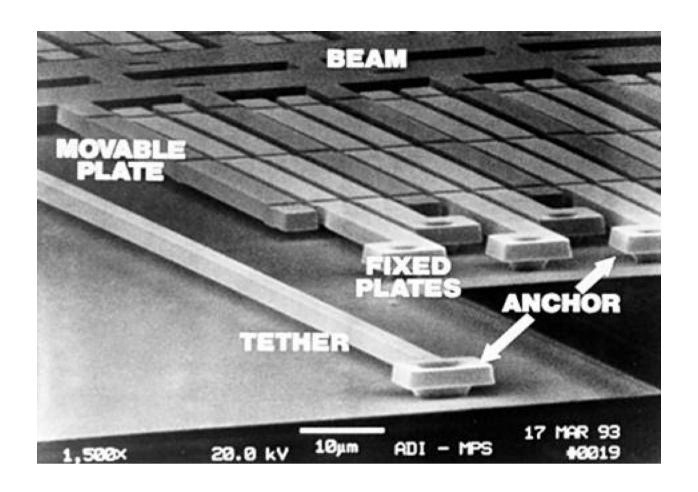
The continuing development of silicon micromechanical applications is only one aspect of the current technical drive toward miniaturization which is being pursued over a wide front in many diverse engineering disciplines. Certainly silicon microelectronics continues to be the most obvious success in the ongoing pursuit of miniaturization. Four factors have played crucial roles in this phenomenal success story: 1) the active material, silicon, is abundant, inexpensive, and can now be produced and processed controllably to unparalleled standards of purity and perfection; 2) silicon processing itself is based on very thin deposited films which are highly amenable to miniaturization; 3) definition and reproduction of the device shapes and patterns are performed using photographic techniques which have also, historically, been capable of high

#### **MEMS**





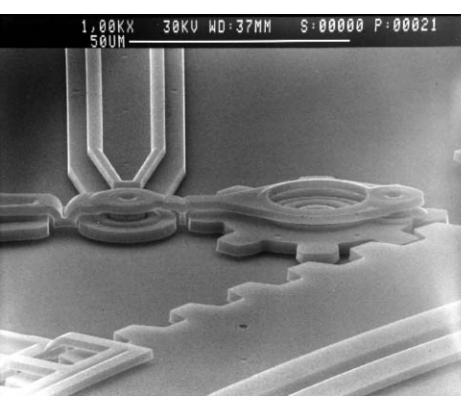
#### **MEMS Acceleration Sensor**

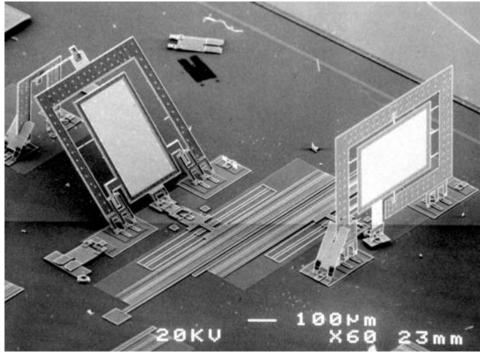




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#### Gears? 3D?





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# **MEMS Process (Example)**

